

Supplies Provided by NUFAB

Gowning

All required gowning supplies

Personal Protective Equipment (PPE)

All required PPE

Chemicals

Photoresists: SPR220.7, SU8-2050, SU8 25, SU8 2, SU8-2010, S1813, S1805, LOR 1A, LOR 5A, AZ 5214E-IR, AZ P4620, 495 PMMA A8, Polyimide PI2545

Developers: MF319, AZ 400K (1:4 and concentrated), SU8 Developer, AZ 917MIF,

Resist Removers: Remover 1165, Nanostrip

Adhesion Promoter: HMDS, MCC Primer 80/20 (20% HMDS and 80% PM Acetate)

Solvents: Acetone, 2-Propanol

Acids: Chrome Etchant, Buffered Oxide Etch 6:1, Aluminum Etchant, Nanostrip, HF, Fe₂O₃ Etchant, Copper Etchant, Gold Etchant TFA

General Cleanroom Supplies

Silicon Wafers (various sizes)

Wafer and Mask Holders (various sizes)

Cleanroom Notebooks

Cleanroom Paper

Cleanroom Wipes (two types)

Storage Boxes

Petri Dishes

Aluminum Foil

Equipment Specific Supplies

AJA Sputter Targets: Cu, Al, Cr, Ti, Ni, W, Si, SiO₂, Si₃N₄, ZnO, ITO, PZT, Zn/Al₂O₃ (2% by weight)

AJA E-beam Evaporator: Crucibles for all materials

Denton Thermal Evaporator: Boats for all materials, chrome-coated tungsten rods

Evaporation Materials: Mo, W, Ag, Al, Cu, Ni, Ti, Cr, Au

Mask and Maskless Aligners: Blank Photomasks (for mask making) 4"x4" (Cr), 5"x5" (Cr), 3"x3" (Fe₂O₃), 4"x4" (Fe₂O₃), 5"x5" (Fe₂O₃)

Gases

Silane, Ammonia, Hydrogen, Dichlorosilane, Forming Gas (4%H₂, Balance N₂), UHP nitrogen, Oxygen, N₂O, CF₄, C₄F₈, CHF₃, Helium, SF₆, Argon, Liquid CO₂